

## Academic Pricing - Tier 2 Special Equipment Rate

Name	Description	Price	Unit
aln2	Tegal Endeavor AT sputter deposition sy	\$0.73	minute
asap-liftoff	Liftoff System - Model ASAP LOM6100	\$0.73	minute
ast-ebeam	AST Electron Beam Dielectric Deposition	\$0.73	minute
ast-sputter	3" Multi-Target Reactive Co-Sputter System	\$0.73	minute
cambridge	Cambridge Fiji F200 Plasma ALD	\$0.73	minute
canon	Canon 4X wafer stepper	\$0.73	minute
centura-3-5	Centura Compound Etch - Chamber A	\$0.73	minute
centura-met	Centura DPS Metal Etcher - Ch C	\$0.73	minute
centura-mxp	Centura oxide etch chamber - Ch B	\$0.73	minute
centura-stri	Centura Stripper - Ch D	\$0.73	minute
cha	CHA E-beam Evaporator	\$0.73	minute
cmp	Strausbaugh Model 6EC CMP	\$0.73	minute
disco	Disco DAD3240 Automated Dicing Saw	\$0.73	minute
ebeam1	Electron Beam 10 kW 4-pocket Evaporator	\$0.73	minute
edwards	Edwards Sputter System	\$0.73	minute
gartek	Gartek sputterer	\$0.73	minute
gcapg	GCA 3600F Pattern Generator	\$0.73	minute
gcaws6	GCA 8500 5X I-line Stepper	\$0.73	minute
gnpcmp	G&P Poli 500 CMP	\$0.73	minute
ionmill6	Pi Scientific 6" Ion Beam Mill	\$0.73	minute
ksaligner	Karl Suss Mask/Bond Aligner	\$0.73	minute
lacvd	Laser Assisted Chemical Vapor Deposition	\$0.73	minute
lam6	Lam 4526 Oxide Etch	\$0.73	minute
lam7	Lam Research 9626 Aluminum Etch	\$0.73	minute
lam8	9426 Lam Research TCP MOS Poly Etch	\$0.73	minute
matrix-etch	Matrix 303 plasma etcher	\$0.73	minute
mrc944	MRC Sputtering System with Sputter-Etch	\$0.73	minute
oxford	Oxford Plasmalab System 100	\$0.73	minute
oxford-icp	Oxford Instruments PlasmaPro100 ICP65	\$0.73	minute
oxford2	Oxford Plasmalab 80 PECVD	\$0.73	minute
oxfordpecvd3	Oxford Cluster Chamber3 PECVD	\$0.73	minute
oxfordpecvd4	Oxford Cluster Chamber4 PECVD	\$0.73	minute
oxfordpvd1	Oxford Cluster Chamber1 Sputter Dep	\$0.73	minute
oxfordpvd2	Oxford Cluster Chamber2 Sputter Dep	\$0.73	minute
park-afm	Atomic force microscope	\$0.73	minute
picosun	Picosun Sunale R150 ALD	\$0.73	minute
picotrack1	Picotrack Coater model PCT-200	\$0.73	minute
picotrack2	PicoTrack Develop model PCT-200	\$0.73	minute
pqecr	Plasma Quest ECR PECVD	\$0.73	minute
ptherm	Plasmatherm reactive ion etcher	\$0.73	minute

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randex	Randex sputtering system	\$0.73	minute
rtp1	AccuThermo AW610 RTP for III/V or PZT	\$0.73	minute
rtp2	AccuThermo AW610 RTP III/V -no metal	\$0.73	minute
rtp3	AccuThermo AW610 RTP Si Non-MOS	\$0.73	minute
rtp4	AccuThermo AW610 RTP Si MOS Clean	\$0.73	minute
rtp8	AccuThermo AW810 RTP Si MOS Clean	\$0.73	minute
semi	Semigroup plasma etcher	\$0.73	minute
sts-oxide	APS deep oxide etch	\$0.73	minute
sts2	ICP pulsed gas deep silicon etch	\$0.73	minute
svgcoat3	SVG 8600 6" LOR & BARC Coat & Bake Track	\$0.73	minute
svgcoat6	SVG 6" Coat Track	\$0.73	minute
svgdev6	SVG8800 6" Develop Track	\$0.73	minute
tystar1	Tystar 6" Wet/Dry Oxidation	\$0.73	minute
tystar10	Tystar LPCVD Doped Poly	\$0.73	minute
tystar11	Tystar LPCVD Doped LTO	\$0.73	minute
tystar12	Tystar Doped LTO	\$0.73	minute
tystar13	Tystar 6" POCL3	\$0.73	minute
tystar14	Tystar 6" Solid-Source Boron	\$0.73	minute
tystar15	Tystar 6" LPCVD Silicon Carbide	\$0.73	minute
tystar16	Tystar 6" Doped Poly LPCVD	\$0.73	minute
tystar17	Tystar LPCVD Low Stress Nitride	\$0.73	minute
tystar18	Tystar 6" MOS Sinter	\$0.73	minute
tystar19	Tystar LPCVD Si/Ge, MOS	\$0.73	minute
tystar2	Tystar 6" Wet/Dry Oxidation	\$0.73	minute
tystar20	Tystar Si/Ge LPCVD for MEMS	\$0.73	minute
tystar3	Tystar 6" Wet/Dry Oxidation	\$0.73	minute
tystar4	Tystar 6" Wet/Dry Oxidation	\$0.73	minute
tystar5	Tystar 200mm Wet/Dry Oxidation	\$0.73	minute
tystar6	Tystar 200mm N-Type Doping	\$0.73	minute
tystar7	Tystar 200mm P-Type Doping	\$0.73	minute
tystar9	Tystar LPCVD Nitride	\$0.73	minute
ultek2	Ultek2 Angled Cooled Chuck E-Beam Evapor	\$0.73	minute
xetch	XeF2 Bulk Silicon Etcher	\$0.73	minute